

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No. : 09/991,196 Confirmation No.: 3908
Applicant : Chih-Chien Liu
Filing Date : November 20, 2001
Title : HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION
PROCESS
Group Art Unit : 1796
Examiner : Sergeant, Rabon A.
Docket No. : 20952.4003
Customer No. : 34313

EFS Web
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO OFFICE ACTION

Sir:

This is in response to the Office Action mailed March 26, 2008. The time for responding to the outstanding Office Action is extended by three months to September 26, 2008. Please amend the application as follows:

Amendments to the Claims are reflected in the listing of claims, which begins on page 2 of this paper.

Remarks begin on page 8 of this paper.